1. Record Nr. UNISA996387537503316

Autore	Child John <1638?-1684.>
Titolo	Moderate message to Quakers, seekers and Socinians, by a friend and well-wisher to them all, or Some arguments offered to clear up three points in difference betwixt them and others .. [[electronic resource] /] / By John Child
Pubbl/distr/stampa	[London, : s.n.], Printed in the year, 1676
Descrizione fisica	[2], 74, [4] p
Soggetti	Baptists - England - Doctrines
Lingua di pubblicazione	Inglese
Formato	Materiale a stampa
Livello bibliografico	Monografia
Note generali	Place of publication suggested by Wing. "Three questions offered to be disputed with John Bunion ...": p. [1] at end. Advertising matter on p. [2]-[4] at end. Reproduction of original in: Friends' Library (London, England).
Sommario/riassunto	eebo-0080

2. Record Nr. UNISA996388209203316

Autore	Crouch John <fl. 1660-1681.>
Titolo	To His Sacred Majestie, loyall reflections upon his glorious restauration, procession and coronation [[electronic resource]] : not forgetting the royal oake
Pubbl/distr/stampa	[S.l., : s.n, 1660?]
Descrizione fisica	[8] p
Soggetti	Great Britain History Restoration, 1660-1688 Poetry
Lingua di pubblicazione	Inglese
Formato	Materiale a stampa
Livello bibliografico	Monografia
Note generali	Signed: J. Crouch. Caption title. In verse. Reproduction of original in the Cambridge University Library.
Sommario/riassunto	eebo-0021

3. Record Nr. UNINA9910317662203321

Autore	Ishaq Ahmad
Titolo	Ion implantation : research and application
Pubbl/distr/stampa	IntechOpen, 2017 [Place of publication not identified] : , : IntechOpen, , 2017 ©2017
ISBN	953-51-4793-5 953-51-3238-5
Descrizione fisica	1 online resource (154 pages)
Disciplina	530
Soggetti	SCIENCE / Mechanics / Thermodynamics
Lingua di pubblicazione	Inglese
Formato	Materiale a stampa
Livello bibliografico	Monografia
Sommario/riassunto	Ion implantation is one of the promising areas of sciences and technologies. It has been observed as a continuously evolving technology. In this book, there is a detailed overview of the recent ion implantation research and innovation along with the existing ion implantation technological issues especially in microelectronics. The book also reviews the basic knowledge of the radiation-induced defects production during the ion implantation in case of a semiconductor structure for fabrication and development of the required perfect microelectronic devices. The improvement of the biocompatibility of biomaterials by ion implantation, which is a hot research topic, has been summarized in the book as well. Moreover, advanced materials characterization techniques are also covered in this book to evaluate the ion implantation impact on the materials.